ABSTRACT OF THE DISCLOSURE

The exposure apparatus comprises: a barometer for detecting air pressure, a lens driving unit for driving a lens of a projection optical system, a light-source-wavelength changing unit for changing a wavelength of an exposure light source, and a stage driving unit for driving a wafer stage in the optical-axis direction. The apparatus can correct an aberration caused by a change in air pressure by utilizing the lens driving unit, light-source-wavelength changing unit, and stage driving unit. During a shot of an exposure of the exposure apparatus, the lens driving unit and/or the stage driving unit are employed to correct the aberration. In the non-exposure state (shot interval), the light-source-wavelength changing unit and/or the lens driving unit as well as the stage driving unit are employed to correct the aberration.